Ellen R Fisher

List of Publications by Year
in descending order

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125	7,184	87888 38	58581 82
papers	citations	h-index	g-index

126	126	126	6771
all docs	docs citations	times ranked	citing authors

#	Article	IF	Citations
1	Engineered Nanoparticle Release from Personal Protective Clothing: Implications for Inhalation Exposure. ACS Applied Nano Materials, 2022, 5, 2558-2568.	5.0	3
2	Employing Optical Emission Spectroscopy to Elucidate the Impact of Titanium Dioxide in Plasma-Assisted Catalysis. Journal of Physical Chemistry C, 2021, 125, 3924-3939.	3.1	6
3	Elucidating energetics and kinetics in environmentally relevant mixed gas plasmas. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2021, 39, 053001.	2.1	1
4	Comparison of CO and CO2 rf plasma treatment of SnO2 nanoparticles for gas sensing materials. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2021, 39, 063005.	2.1	1
5	Tailoring the surface properties of porous zeolite constructs using plasma processing. Microporous and Mesoporous Materials, 2020, 307, 110467.	4.4	2
6	Efforts Toward Unraveling Plasma-Assisted Catalysis: Determination of Kinetics and Molecular Temperatures within N2O Discharges. ACS Catalysis, 2020, 10, 6546-6560.	11.2	5
7	Utilizing plasma modified SnO2 paper gas sensors to better understand gas-surface interactions at low temperatures. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2020, 38, .	2.1	7
8	Investigating recent developments and applications of optical plasma spectroscopy: A review. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2020, 38, .	2.1	20
9	Gas-phase diagnostic studies of H2 and CH4 inductively coupled plasmas. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2020, 38, 033010.	2.1	3
10	Investigating the impact of catalysts on N₂ rotational and vibrational temperatures in low pressure plasmas. Journal Physics D: Applied Physics, 2019, 52, 345202.	2.8	11
11	Time of flight secondary ion mass spectrometryâ€"A method to evaluate plasma-modified three-dimensional scaffold chemistry. Biointerphases, 2018, 13, 03B415.	1.6	7
12	Perspectives on antibacterial performance of silver nanoparticle-loaded three-dimensional polymeric constructs. Biointerphases, 2018, 13, 06E404.	1.6	2
13	Determination of rotational and vibrational temperatures of CH in CH4 plasmas. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2018, 36, .	2.1	7
14	Investigations of fundamental nitrogen oxide plasma chemistry & surface interactions. , 2018, , .		0
15	The Effect of Ar/O₂ and H₂O Plasma Treatment of SnO₂ Nanoparticles and Nanowires on Carbon Monoxide and Benzene Detection. ACS Applied Materials & Interfaces, 2017, 9, 15733-15743.	8.0	27
16	Using Fundamental Spectroscopy to Elucidate Kinetic and Energetic Mechanisms within Environmentally Relevant Inductively Coupled Plasma Systems. Journal of Physical Chemistry A, 2017, 121, 7627-7640.	2.5	10
17	Investigation of Antibacterial 1,8-Cineole-Derived Thin Films Formed via Plasma-Enhanced Chemical Vapor Deposition. ACS Applied Materials & Interfaces, 2017, 9, 36548-36560.	8.0	19
18	Gas-phase diagnostics during H2 and H2O plasma treatment of SnO2 nanomaterials: Implications for surface modification. Journal of Vacuum Science and Technology B:Nanotechnology and Microelectronics, 2017, 35, 021802.	1.2	7

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19	Energy partitioning and its influence on surface scatter coefficients within fluorinated inductively coupled plasmas. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2017, 35, .	2.1	8
20	Determination of internal temperatures within nitric oxide inductively coupled plasmas. Plasma Processes and Polymers, 2017, 14, 1700041.	3.0	10
21	Modification of a commercial thromboelastography instrument to measure coagulation dynamics with three-dimensional biomaterials. Biointerphases, 2016, 11, 029602.	1.6	3
22	Plasma-modified nitric oxide-releasing polymer films exhibit time-delayed 8-log reduction in growth of bacteria. Biointerphases, 2016, 11, 031005.	1.6	13
23	In-Depth View of the Structure and Growth of SnO₂ Nanowires and Nanobrushes. ACS Applied Materials & Interfaces, 2016, 8, 22345-22353.	8.0	18
24	Hydrophilic Modification of Polysulfone Ultrafiltration Membranes by Low Temperature Water Vapor Plasma Treatment to Enhance Performance. Plasma Processes and Polymers, 2016, 13, 598-610.	3.0	31
25	Innovative Applications of Surface Wettability Measurements for Plasmaâ€Modified Threeâ€Dimensional Porous Polymeric Materials: A Review. Plasma Processes and Polymers, 2015, 12, 846-863.	3.0	20
26	Allylamine and Allyl Alcohol Plasma Copolymerization: Synthesis of Customizable Biologicallyâ€Reactive Threeâ€Dimensional Scaffolds. Plasma Processes and Polymers, 2015, 12, 1435-1450.	3.0	7
27	Evaluation of polymer hydrophobic recovery behavior following H₂O plasma processing. Journal of Applied Polymer Science, 2015, 132, .	2.6	26
28	N₂/H₂o Plasma Assisted Functionalization of Poly(Îµâ€caprolactone) Porous Scaffolds: Acidic/Basic Character versus Cell Behavior. Plasma Processes and Polymers, 2015, 12, 786-798.	3.0	14
29	Ar/O2 and H2O plasma surface modification of SnO2 nanomaterials to increase surface oxidation. Sensors and Actuators B: Chemical, 2015, 208, 379-388.	7.8	33
30	Etching and Postâ€Treatment Surface Stability of Trackâ€Etched Polycarbonate Membranes by Plasma Processing Using Various Related Oxidizing Plasma Systems. Plasma Processes and Polymers, 2014, 11, 850-863.	3.0	20
31	Conformal Encapsulation of Three-Dimensional, Bioresorbable Polymeric Scaffolds Using Plasma-Enhanced Chemical Vapor Deposition. Langmuir, 2014, 30, 12328-12336.	3.5	22
32	NH₂ and NH Surface Production in Pulsed NH₃ Plasmas on TiO₂: A Steadyâ€State Probe of Short Pulse Plasmas. Plasma Processes and Polymers, 2013, 10, 6-18.	3.0	6
33	Design and operation of a rotating drum radio frequency plasma reactor for the modification of free nanoparticles. Review of Scientific Instruments, 2013, 84, 063904.	1.3	7
34	Effect of Ion Energies on the Surface Interactions of NO Formed in Nitrogen Oxide Plasma Systems. Journal of Physical Chemistry A, 2013, 117, 1204-1215.	2.5	4
35	H2O plasma modification of track-etched polymer membranes for increased wettability and improved performance. Journal of Membrane Science, 2013, 428, 576-588.	8.2	53
36	Challenges in the Characterization of Plasma-Processed Three-Dimensional Polymeric Scaffolds for Biomedical Applications. ACS Applied Materials & Interfaces, 2013, 5, 9312-9321.	8.0	22

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37	Enhancing Surface Functionality of Supported Fe₂O₃ Nanoparticles Using Pulsed Plasma Deposition of Allyl Alcohol. Nanoscience and Nanotechnology Letters, 2013, 4, 358-363.	0.4	4
38	Plasma Synthesis of Hydrocarbon/<scp>F</scp>luorocarbon Thin Films with Compositional Gradients. Plasma Processes and Polymers, 2013, 10, 779-791.	3.0	10
39	Ion contributions to gasâ€“surface interactions in inductively-coupled fluorocarbon plasmas. International Journal of Mass Spectrometry, 2012, 330-332, 46-57.	1.5	6
40	Contributions of CF and CF₂ Species to Fluorocarbon Film Composition and Properties for C_xF_y Plasma-Enhanced Chemical Vapor Deposition. ACS Applied Materials & Interfaces, 2012, 4, 1733-1741.	8.0	26
41	Comparing Isoelectric Point and Surface Composition of Plasma Modified Native and Deposited SiO₂ Films Using Contact Angle Titrations and Xâ€ray Photoelectron Spectroscopy. Plasma Processes and Polymers, 2011, 8, 951-964.	3.0	14
42	Isoelectric points of plasmaâ€modified and aged silicon oxynitride surfaces measured using contact angle titrations. Surface and Interface Analysis, 2011, 43, 1257-1270.	1.8	12
43	Composite SiO2/TiO2 and amine polymer/TiO2 nanoparticles produced using plasma-enhanced chemical vapor deposition. Applied Surface Science, 2010, 256, 2081-2091.	6.1	30
44	Pulsed Plasma Enhanced Chemical Vapor Deposition of Poly(allyl alcohol) onto Natural Fibers. Plasma Processes and Polymers, 2010, 7, 695-707.	3.0	15
45	Investigation of the roles of gas-phase CF2 molecules and F atoms during fluorocarbon plasma processing of Si and ZrO2 substrates. Journal of Applied Physics, 2010, 108, 033303.	2.5	13
46	Controlled Nitrogen Doping and Film Colorimetrics in Porous TiO₂ Materials Using Plasma Processing. ACS Applied Materials & Interfaces, 2010, 2, 1743-1753.	8.0	52
47	Gas-Phase Chemistry in Inductively Coupled Plasmas for NO Removal from Mixed Gas Systems. Journal of Physical Chemistry A, 2010, 114, 1722-1733.	2.5	21
48	Gas Phase Energetics of CN Radicals in Radio Frequency Discharges: Influence on Surface Reaction Probability During Deposition of Carbon Nitride Films. Journal of Physical Chemistry A, 2010, 114, 5287-5294.	2.5	5
49	Detection Limits and Decomposition Mechanisms for Organic Contaminants in Water Using Optical Emission Spectroscopy. Plasma Processes and Polymers, 2009, 6, 180-189.	3.0	10
50	O2 plasma treatment of mesoporous and compact TiO2 photovoltaic films: Revealing and eliminating effects of Si incorporation. Surface and Coatings Technology, 2009, 203, 2236-2242.	4.8	13
51	Comparison of CH, C₃, CHF, and CF₂ Surface Reactivities during Plasma-Enhanced Chemical Vapor Deposition of Fluorocarbon Films. ACS Applied Materials & Interfaces, 2009, 1, 934-943.	8.0	8
52	CN Surface Interactions and Temperature-Dependent Film Growth During Plasma Deposition of Amorphous, Hydrogenated Carbon Nitride. Journal of Physical Chemistry C, 2009, 113, 1963-1971.	3.1	18
53	Pulsedâ€Plasmaâ€Induced Micropatterning with Alternating Hydrophilic and Hydrophobic Surface Chemistries. Plasma Processes and Polymers, 2008, 5, 129-145.	3.0	28
54	Plasma Diagnostics for Unraveling Process Chemistry. Annual Review of Analytical Chemistry, 2008, 1, 261-291.	5.4	35

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55	Synthesis of LaPO₄:Eu Nanostructures Using the Solâ"Gel Template Method. Journal of Physical Chemistry C, 2008, 112, 1901-1907.	3.1	54
56	A Directed Framework for Integrating Ethics into Chemistry Curricula and Programs Using Real and Fictional Case Studies. Journal of Chemical Education, 2008, 85, 796.	2.3	18
57	Correlation of gas-phase composition with film properties in the plasma-enhanced chemical vapor deposition of hydrogenated amorphous carbon nitride films. Journal of Applied Physics, 2007, 101, 023304.	2.5	21
58	Plasma Modification of PDMS Microfluidic Devices for Control of Electroosmotic Flow. Plasma Processes and Polymers, 2007, 4, 414-424.	3.0	30
59	Surface Reactivity and Energetics of CH Radicals during Plasma Deposition of Hydrogenated Diamondlike Carbon Films. Journal of Physical Chemistry B, 2006, 110, 21911-21919.	2.6	15
60	Radical-surface interactions during film deposition: A sticky situation?. Pure and Applied Chemistry, 2006, 78, 1187-1202.	1.9	28
61	Investigation of Gas Phase Species and Deposition of SiO2 Films from HMDSO/O2 Plasmas. Plasma Processes and Polymers, 2006, 3, 276-287.	3.0	96
62	Investigation of inductively coupled Ar and CH4/Ar plasmas and the effect of ion energy on DLC film properties. Plasma Sources Science and Technology, 2006, 15, 714-726.	3.1	48
63	Correlating ion energies and CF2 surface production during fluorocarbon plasma processing of silicon. Journal of Applied Physics, 2006, 100, 013301.	2.5	17
64	Surface modification with nitrogen-containing plasmas to produce hydrophilic, low-fouling membranes. Journal of Membrane Science, 2005, 246, 203-215.	8.2	219
65	Modification of polysulfone ultrafiltration membranes by CO2 plasma treatment. Desalination, 2005, 172, 189-205.	8.2	149
66	Chemical surface treatment of ultrahigh molecular weight polyethylene for improved adhesion to methacrylate resins. Journal of Applied Polymer Science, 2005, 96, 1564-1572.	2.6	51
67	Examination of Size-Induced Ferroelectric Phase Transitions in Template Synthesized PbTiO3 Nanotubes and Nanofibers. Chemistry of Materials, 2005, 17, 5909-5919.	6.7	70
68	Comparison of pulsed and downstream deposition of fluorocarbon materials from C3F8 and c-C4F8 plasmas. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2004, 22, 227-235.	2.1	53
69	Mechanisms of SiO2 film deposition from tetramethylcyclotetrasiloxane, dimethyldimethoxysilane, and trimethylsilane plasmas. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2004, 22, 201-213.	2.1	29
70	Creation of SiOF films with SiF4/O2 plasmas: From gas-surface interactions to film formation. Journal of Applied Physics, 2004, 96, 1094-1103.	2.5	18
71	Ion effects on CF2 surface interactions during C3F8 and C4F8 plasma processing of Si. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2004, 22, 2168-2176.	2.1	40
72	A Review of Plasma-Surface Interactions During Processing of Polymeric Materials Measured Using the IRIS Technique. Plasma Processes and Polymers, 2004, 1, 13-27.	3.0	35

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73	Investigation of the PECVD TiO2â€“Si(100) interface. Applied Surface Science, 2004, 233, 69-79.	6.1	51
74	Surface Reactivity of OH Molecules during Deposition of SiO2 from Siloxane-Based Plasmas. Journal of Physical Chemistry B, 2004, 108, 9821-9828.	2.6	5
75	Membrane Surface Modification by Plasma-Induced Polymerization of Acrylamide for Improved Surface Properties and Reduced Protein Fouling. Langmuir, 2003, 19, 79-85.	3.5	296
76	Velocity Distributions of SiF and SiF2in an SiF4Plasma Molecular Beam. Journal of Physical Chemistry A, 2003, 107, 593-597.	2.5	11
77	Mechanisms for deposition and etching in fluorosilane plasma processing of silicon. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2003, 21, 1688-1701.	2.1	18
78	On the interplay between plasma ions, radicals and surfaces: who dominates the interaction?. Plasma Sources Science and Technology, 2002, 11, A105-A112.	3.1	26
79	Hydrophilic Surface Modification of Microporous Polymer Membranes Using A Variety of Low-Temperature Plasma Treatments. Materials Research Society Symposia Proceedings, 2002, 752, 1.	0.1	3
80	Surface Reactivity and Plasma Energetics of SiH Radicals during Plasma Deposition of Silicon-Based Materials. Journal of Physical Chemistry B, 2002, 106, 2680-2689.	2.6	27
81	Comparison of surface interactions for NH and NH2 on polymer and metal substrates during NH3 plasma processing. Journal of Applied Physics, 2002, 92, 55-63.	2.5	34
82	Solâ”Gel Template Synthesis and Characterization of BaTiO3 and PbTiO3 Nanotubes. Chemistry of Materials, 2002, 14, 480-482.	6.7	291
83	On the importance of ions and ion-molecule reactions to plasma-surface interface reactions. Journal of the American Society for Mass Spectrometry, 2002, 13, 518-529.	2.8	48
84	Hydrophilic modification of polymeric membranes by low temperature H2O plasma treatment. Journal of Membrane Science, 2002, 204, 341-357.	8.2	211
85	Hydrophilic modification of polyethersulfone membranes by low temperature plasma-induced graft polymerization. Journal of Membrane Science, 2002, 209, 255-269.	8.2	368
86	Modification of porous poly(ether sulfone) membranes by low-temperature CO2-plasma treatment. Journal of Polymer Science, Part B: Polymer Physics, 2002, 40, 2473-2488.	2.1	43
87	Identification of Gas-Phase Reactive Species and Chemical Mechanisms Occurring at Plasmaâ”Polymer Surface Interfaces. Langmuir, 2001, 17, 8156-8166.	3.5	52
88	Plasma Modification of Porous Structures for Formation of Composite Materials. Chemistry of Materials, 2001, 13, 2749-2752.	6.7	32
89	Mechanisms and Energy Transfer for Surface Generation of NH2 during NH3 Plasma Processing of Metal and Polymer Substrates. Journal of Physical Chemistry B, 2001, 105, 5957-5967.	2.6	39
90	Low temperature plasma treatment of asymmetric polysulfone membranes for permanent hydrophilic surface modification. Journal of Membrane Science, 2001, 188, 97-114.	8.2	178

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91	Surface Interactions of CF₂ Radicals during Deposition of Amorphous Fluorocarbon Films. ACS Symposium Series, 2001, , 168-186.	0.5	5
92	Ion and substrate effects on surface reactions of CF2 using C2F6, C2F6/H2, and hexafluoropropylene oxide plasmas. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2000, 18, 2685-2698.	2.1	41
93	Deposition of Highly Ordered CF2-Rich Films Using Continuous Wave and Pulsed Hexafluoropropylene Oxide Plasmas. Chemistry of Materials, 2000, 12, 2014-2024.	6.7	99
94	Pulsed and continuous wave plasma deposition of amorphous, hydrogenated silicon carbide from SiH4/CH4 plasmas. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 1999, 17, 2475-2484.	2.1	16
95	Surface Interactions of Radicals During Plasma Processing of Polymers. Plasmas and Polymers, 1999, 4, 77-91.	1.5	17
96	An Electrochemically Driven Actuator Based on a Nanostructured Carbon Material. Analytical Chemistry, 1999, 71, 3187-3191.	6.5	18
97	Surface Interactions of NH2Radicals in NH3Plasmas. Journal of Physical Chemistry B, 1999, 103, 6919-6929.	2.6	46
98	Metal-Nanocluster-Filled Carbon Nanotubes:Â Catalytic Properties and Possible Applications in Electrochemical Energy Storage and Production. Langmuir, 1999, 15, 750-758.	3.5	405
99	Title is missing!. Plasmas and Polymers, 1998, 3, 197-209.	1.5	35
100	Carbon nanotubule membranes for electrochemical energy storage and production. Nature, 1998, 393, 346-349.	27.8	1,757
101	Characterization of Pulsed-Plasma-Polymerized Aromatic Films. Langmuir, 1998, 14, 1227-1235.	3.5	123
102	Pulsed Plasma Polymerization of Benzaldehyde for Retention of the Aldehyde Functional Group. Macromolecules, 1998, 31, 7618-7626.	4.8	39
103	Surface interactions of CF2 radicals during deposition of amorphous fluorocarbon films from CHF3 plasmas. Journal of Applied Physics, 1998, 84, 4736-4743.	2.5	68
104	Comparison of Oxidation Rates for aâ€‰â€â€‰Si1â€‰â^'â€‰x â€‰Câ€‰ x â€‰:â€‰â€‰Hâ€‰ Films Deposited from Pulsed an Plasmas. Journal of the Electrochemical Society, 1998, 145, 3271-3277.	2.9	13
105	Deposition of SiO2 films from novel alkoxysilane/O2 plasmas. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 1998, 16, 3175-3184.	2.1	32
106	Fabrication and characterization of concentric-tubular composite micro- and nanostructures using the template-synthesis method. Journal of Materials Research, 1998, 13, 3070-3080.	2.6	57
107	A modified molecular beam instrument for the imaging of radicals interacting with surfaces during plasma processing. Review of Scientific Instruments, 1997, 68, 1684-1693.	1.3	71
108	Comparison of Pulsed and Continuous-Wave Deposition of Thin Films from Saturated Fluorocarbon/H2Inductively Coupled rf Plasmas. Chemistry of Materials, 1997, 9, 349-362.	6.7	127

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109	Chemical Strategies for Template Syntheses of Composite Micro- and Nanostructures. Chemistry of Materials, 1997, 9, 1065-1067.	6.7	108
110	Surface Reactivity of CF2Radicals Measured Using Laser-Induced Fluorescence and C2F6Plasma Molecular Beams. Journal of Physical Chemistry B, 1997, 101, 9425-9428.	2.6	37
111	Effects of Plasma Processing Parameters on the Surface Reactivity of OH(X2Î) in Tetraethoxysilane/O2Plasmas during Deposition of SiO2. Journal of Physical Chemistry B, 1997, 101, 10016-10023.	2.6	43
112	A versatile substrate heater for thermal and plasma-enhanced chemical-vapor deposition. Review of Scientific Instruments, 1997, 68, 2149-2155.	1.3	7
113	Velocity distributions of NH2 radicals in an NH3 plasma molecular beam. Chemical Physics Letters, 1997, 274, 120-126.	2.6	24
114	Probing the [CoC2H6]+Potential Energy Surface:Â A Detailed Guided-Ion Beam Study. Journal of the American Chemical Society, 1996, 118, 3269-3280.	13.7	33
115	Probing the [CoC3H8]+ Potential Energy Surface:â€‰ A Detailed Guided-Ion Beam Study. The Journal of Physical Chemistry, 1996, 100, 18300-18316.	2.9	28
116	Plasma enhanced chemical vapor deposition of SiO2 using novel alkoxysilane precursors. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 1995, 13, 476-480.	2.1	76
117	Dissociative charge-transfer reactions of atomic nitrogen (1+) (3P), dinitrogen (1+) (2.SIGMA.g+), argon(1+) (2P3/2,1/2), and krypton(1+) (2P3/2) with tetrafluorosilane. Thermochemistry of SiF4+ and SiF3+. The Journal of Physical Chemistry, 1993, 97, 10198-10203.	2.9	24
118	Guided ion beam studies of the reaction of silicon(1+) (2P) with methylsilane: reaction mechanisms and thermochemistry of organosilicon species. The Journal of Physical Chemistry, 1992, 96, 2603-2609.	2.9	19
119	Collisionâ€induced dissociation and charge transfer reactions of SF+x(x=1â€“5): Thermochemistry of sulfur fluoride ions and neutrals. Journal of Chemical Physics, 1992, 97, 4859-4870.	3.0	109
120	Kinetic energy dependence of the reactions of atomic oxygen(1+) and dioxygenyl ion with tetrafluoromethane and hexafluoroethane. The Journal of Physical Chemistry, 1991, 95, 6118-6124.	2.9	22
121	Translational and internal energy effects in reactions of O+ and O+2 with SiF4. Chemical Physics Letters, 1991, 179, 435-441.	2.6	10
122	Reactions of oxygen(+), argon(+), neon(+), and helium(+) with tetrachlorosilane: thermochemistry of chlorosilanes (SiClx+; X = 1-3). The Journal of Physical Chemistry, 1991, 95, 4765-4772.	2.9	22
123	The appearance energy of CF+3 from CF4: ion/molecule reactions related to the thermochemistry of CF+3. International Journal of Mass Spectrometry and Ion Processes, 1990, 101, R1-R6.	1.8	42
124	Dissociative charge transfer reactions of Ar+, Ne+, and He+ with CF4 from thermal to 50 eV. Journal of Chemical Physics, 1990, 92, 2296-2302.	3.0	78
125	Kinetic energy dependence of dissociative chargeâ€“transfer reactions of He+, Ne+, Ar+, Kr+, and Xe+ with silane. Journal of Chemical Physics, 1990, 93, 4858-4867.	3.0	33